



IFW

PATENT
Docket No. 506212001200

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the application of:

Michihiko YANAGISAWA et al.

Serial No.: 10/671,483

Filing Date: September 29, 2003

For: MULTI-STEP DRY ETCHING
METHOD FOR SOI WAFER

Examiner: Fernando L. Toledo

Group Art Unit: 2823

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

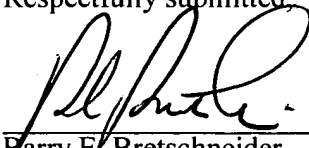
In response to the Action dated September 9, 2004, Applicants elect to prosecute apparatus claims 5 and 6, Group II, without traverse. Applicants authorize the Examiner to cancel non-elected claims 1-4 upon the indication of allowable subject matter in this application.

Early action allowing claims 5 and 6 is solicited. Please charge any fees that may occur to our Deposit Account No. 03-1952 referencing 506212001200.

Respectfully submitted,

Dated: September 20, 2004

By:


Barry E. Bretschneider
Registration No. 28,055

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